

Amendments to the Claims:

Please cancel claim 2 without prejudice or disclaimer.

Claims 1, 13, 14 and 15 have been amended herein. Please note that all claims currently pending and under consideration in the referenced application are shown below. Please enter these claims as amended. This listing of claims will replace all prior versions and listings of claims in the application.

Listing of Claims:

1. (Previously Presented) A substrate for testing at least one semiconductor device having at least one substantially spherical interconnection element protruding from a surface thereof, comprising consisting essentially of:
a semiconductor substrate having a dielectric layer on an exposed surface thereof;
at least one conductive trace on over the dielectric layer;
a passivation layer over the at least one conductive trace and the dielectric layer; and
a metal-lined via in-extending through the passivation layer to a portion of the at least one conductive trace, wherein the metal of the metal-lined via is in electrical communication with the at least one conductive trace, wherein the metal-lined via is sized and configured to receive, without deformation, the at least one substantially spherical interconnection element protruding from the at least one semiconductor device to a depth corresponding to approximately 10% to 50% of an overall height of the substantially spherical interconnection element and temporarily establish an electrical connection therewith at the depth by way of biased contact of only a portion of an interior surface of the metal-lined via against a with only a portion of an exterior surface of the substantially spherical interconnection element received therewithin attached to a semiconductor device.
2. (Canceled).

3. (Currently Amended) The substrate of claim 21, wherein the metal-lined via is formed of a size and shape to receive approximately 30% of the overall height of the substantially spherical interconnection element.

4. (Previously Presented) The substrate of claim 1, wherein the metal-lined via includes sloped sidewalls.

5. (Withdrawn) The substrate of claim 1, wherein the metal-lined via includes stepped sidewalls.

6. (Previously Presented) The substrate of claim 1, wherein the at least one conductive trace comprises copper.

7. (Previously Presented) The substrate of claim 1, wherein the passivation layer comprises polyimide.

8. (Previously Presented) The substrate of claim 1, wherein the metal-lined via comprises a metal from the group comprising gold, platinum, palladium, and tungsten.

9. (Previously Presented) The substrate of claim 1, wherein the dielectric layer comprises silicon dioxide.

10. (Previously Presented) The substrate of claim 1, wherein the passivation layer has a thickness of about 20 to 25 microns.

11. (Previously Presented) The substrate of claim 1, wherein the passivation layer has a thickness of about 100 microns.

12. (Withdrawn) The substrate of claim 1, further comprising:

at least one additional conductive trace over the passivation layer;
a second passivation layer over the at least one additional conductive trace; and
a second metal-lined via in the second passivation layer in electrical communication with the at
least one additional conductive trace.

13. (Currently Amended) The substrate of claim 1, wherein the metal-lined via is sized and configured to ~~temporarily establish the electrical connection comprising a discrete interconnection at only along a~~ at least one contact line consisting of the portion of the interior surface of the metal-lined via at least partially circling ~~the portion of the exterior surface of the~~ substantially spherical interconnection element.

14. (Currently Amended) The substrate of claim 131, wherein the metal-lined via is sized and configured to ~~temporarily establish the electrical connection comprising the discrete interconnection at only along a plurality of contact lines consisting of the portion of the interior surface of the metal-lined via at least partially circling the portion of the exterior surface of the~~ substantially spherical interconnection element.

15. (Currently Amended) The substrate of claim 14, wherein ~~the metal-lined via is sized and configured to temporarily establish the electrical connection comprising the discrete interconnection at the plurality of contact lines at least partially circling comprise the a~~ plurality of contact lines circling the substantially spherical interconnection element.